

	Hits	Search Text	DBs
38	5	(lithography or photolithograph\$3) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3 or platen) same (photosensitive or photoresist or resist)) and (pattern\$4 same (mask or reticle or photomask)) and (plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV or laser) and (gas\$3 same (plasma or ion\$3beam or beam or laser or ion\$4assist\$5 or ion\$4beam) same ((fluoroalkane or fluorin\$4 or bromine or halogen or perhalogenat\$3 or tetrafluoromethane) near16 (alkane or methane or ethane or propane or butane or pentane)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
39	10	((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3 or platen) same (photosensitive or photoresist or resist)) and (pattern\$4 same (mask or reticle or photomask)) and (plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV or laser) and (gas\$3 same (plasma or ion\$3beam or beam or laser or ion\$4assist\$5 or ion\$4beam) same ((fluoroalkane or fluorin\$4 or bromine or halogen or perhalogenat\$3 or tetrafluoromethane) near16 (alkane or methane or ethane or propane or butane or pentane)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
40	10	((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3 or platen) same (photosensitive or photoresist or resist)) and (pattern\$4 same (mask or reticle or photomask)) and (plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV or laser) and (gas\$3 same (plasma or ion\$3beam or beam or laser or ion\$4assist\$5 or ion\$4beam) same ((fluoroalkane or fluorin\$4 or bromine or halogen or (halogenated near9 alkane) or perhalogenat\$3 or tetrafluoromethane) near16 (alkane or methane or ethane or propane or butane or pentane)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
41	12	((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3 or platen) same (photosensitive or photoresist or resist)) and (pattern\$4 same (mask or reticle or photomask)) and (plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV or laser) and (gas\$3 same (plasma or ion\$3beam or beam or laser or ion\$4assist\$5 or ion\$4beam) same ((fluoroalkane or fluorin\$4 or bromine or halogen or (halogenated near9 alkane) or perhalogenat\$3 or tetrafluoromethane) near29 (alkane or methane or ethane or propane or butane or pentane)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
42	17	((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3 or platen or table) same (photosensitive or photoresist or resist)) and (pattern\$4 same (mask or reticle or photomask)) and (plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV or laser) and ((plasma or ion\$3beam or beam or laser or ion\$4assist\$5 or ion\$4beam) same ((fluoroalkane or fluorin\$4 or bromine or halogen or (halogenated near9 alkane) or perhalogenat\$3 or tetrafluoromethane) near36 (alkane or methane or ethane or propane or butane or pentane)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
43	0	((plasma or ion\$3beam or beam or laser or ion\$4assist\$5 or ion\$4beam) same (remov\$3 or etch\$4 or clean\$4 or strip\$4) same (defect\$2 or contaminant\$3 or residu\$5) same (project\$4 or optical or lithographic) same ((fluoroalkane or fluorin\$4 or bromine or halogen or (halogenated near9 alkane) or perhalogenat\$3 or tetrafluoromethane) near36 (alkane or methane or ethane or propane or butane or pentane)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
44	0	((plasma or ion\$3beam or beam or laser or ion\$4assist\$5 or ion\$4beam) same (remov\$3 or etch\$4 or clean\$4 or strip\$4) same (defect\$2 or contaminant\$3 or residu\$5) same ((fluoroalkane or fluorin\$4 or bromine or halogen or (halogenated near9 alkane) or perhalogenat\$3 or tetrafluoromethane) near36 (alkane or methane or ethane or propane or butane or pentane))) and ((project\$4 near9 optic\$4) or (project\$4 near9 system))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
45	15	((plasma or ion\$3beam or beam or laser or ion\$4assist\$5 or ion\$4beam) same (remov\$3 or etch\$4 or clean\$4 or strip\$4) same (defect\$2 or contaminant\$3 or residu\$5) same ((fluoroalkane or fluorin\$4 or bromine or halogen or (halogenated near9 alkane) or perhalogenat\$3 or tetrafluoromethane) near36 (alkane or methane or ethane or propane or butane or pentane)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB